

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A liquid crystal panel substrate, comprising:
 - reflecting electrodes formed on a substrate;
 - a switching element formed corresponding to each of the reflecting electrodes;
 - a passivation film formed on said reflecting electrodes comprising a silicon oxide film; and

a silicon nitride film formed as an insulating interlayer between said reflecting electrodes and a metal shielding layer above the switching element thereunder ~~having moisture resistance, wherein the metal layer shields incident light to the switching element.~~

2. (Original) A liquid crystal panel substrate according to claim 1, wherein said insulating interlayer between said reflecting electrodes and said metal layer thereunder comprises a silicon nitride film and a silicon oxide film, and has a laminate structure in which said silicon nitride film is formed on said silicon oxide film.

3. (Currently Amended) A liquid crystal panel substrate comprising:
 - a pixel region having a matrix of reflecting electrodes formed on a substrate and a switching element formed corresponding to each of said reflecting electrodes, a periphery region of said pixel region on the substrate having at least insulating interlayers; and

a passivation film having a laminate structure comprising a silicon oxide film and a silicon nitride film on said silicon oxide film, the passivation film being formed at least on a thickness side of edge sections of the at least insulating interlayers.

4. (Currently Amended) A liquid crystal panel substrate comprising:

a pixel region having a matrix of reflecting electrodes formed on a substrate and a transistor formed corresponding to each of the reflecting electrodes;

a peripheral circuit arranged in a periphery region of said pixel region on the substrate for supplying signals to said transistors in said pixel region;

a first passivation film comprising a silicon oxide film formed on said reflecting electrodes in said pixel region; and

a second passivation film comprising a silicon nitride film formed at least on a thickness side of edge sections of said periphery region.

7 — 5. (Original) A liquid crystal panel substrate according to claim 4, the silicon nitride film being a first silicon nitride film, the liquid crystal panel substrate further comprising a second silicon nitride film as an insulating interlayer provided between said reflecting electrodes and a metal layer thereunder.

8 — 6. (Original) A liquid crystal panel substrate according to claim 5, the silicon oxide film being a first silicon oxide film, said insulating interlayer between said reflecting electrodes and said metal layer thereunder comprising the second silicon nitride film and a second silicon oxide film, and having a laminate structure in which said second silicon nitride film is formed on said second silicon oxide film.

9 — 7. (Original) A liquid crystal panel substrate comprising:
a pixel region having a matrix of reflecting electrodes formed on a substrate and transistor formed corresponding to each of the reflecting electrodes;
a peripheral circuit arranged in a periphery region of said pixel region on the substrate for supplying signals to said transistors in said pixel region, the periphery region having a metal layer and an insulating layer;

a first passivation film comprising a first silicon oxide film formed in said pixel region; and

a second passivation film having a laminate structure comprising a second silicon oxide film and a silicon nitride film formed on the second silicon oxide film, the second passivation film being formed at edge sections of the metal layer and the insulating interlayer.

4 8. (Original) A liquid crystal panel substrate according to claim 3, further comprising a seal material formed on said silicon nitride film for sealing with a counter substrate.

5 9. (Previously Presented) A liquid crystal panel substrate according to claim 3, said edge section of said insulating interlayers being a scribed region of the substrate.

11 10. (Currently Amended) A liquid crystal panel substrate comprising:
a pixel region having reflecting electrodes formed on a semiconductor substrate and a switching element formed corresponding to each of the reflecting electrodes;
a scribed region formed on the periphery of the pixel region; and
a passivation film formed by a silicon nitride film having moisture resistance
and formed on at the scribed region of said semiconductor substrate.

12 11. (Original) A liquid crystal panel substrate according to claim 10, said passivation film having a laminate structure comprising a silicon oxide film and the silicon nitride film formed on the silicon oxide film.

13 12. (Currently Amended) A liquid crystal panel, comprising:
a first substrate;
a second substrate opposed to the first substrate;
a liquid crystal therebetween, and
a seal material sealing the first substrate and the second substrate;

a pixel region having reflecting electrodes formed on said first substrate; and
a scribed region formed on the periphery of the pixel region; and
a passivation film comprising a silicon nitride film formed ~~in~~on the scribed
region and a region arranged with said seal material on said first substrate, the seal material
being ~~formed~~arranged on the silicon nitride, and the passivation film extending on a scribed
region of the first substrate film.

14 — 13. (Original) A liquid crystal panel according to claim 12, the passivation film being a first passivation film and the liquid crystal panel further comprising a second passivation film comprising a silicon oxide film formed on the reflecting electrodes.

15 — 14. (Currently Amended) A liquid crystal panel substrate, comprising:
reflecting electrodes formed on a substrate ~~having a space between adjacent~~
reflecting electrodes;

a switching element formed corresponding to each of the reflecting electrodes;
a passivation film formed on the reflecting electrodes comprising a silicon
oxide film; and

a light shielding layer disposed under the reflecting electrodes and the space
between adjacent reflecting electrodes so as to cover the switching element; and
a silicon nitride film formed as an insulating interlayer between the reflecting
electrodes and the ~~switching element~~light shielding layer so as to cover the switching element
except for a connection portion connecting between the reflecting electrode and the switching
element.

10 — 15. (Previously Presented) The liquid crystal substrate according to claim 7, the second silicon oxide layer being the same layer as the first silicon oxide layer.